

IPW

PATENT
0941-0754P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: LEE, Brian S. et al. Conf.: 7276
Appl. No.: 10/600,466 Group: 2811
Filed: June 23, 2003 Examiner: D. W. Owens
For: SEMICONDUCTOR DEVICE WITH LOOP LINE PATTERN
STRUCTURE METHOD AND ALTERNATING PHASE SHIFT MASK
FOR FABRICATING THE SAME

LARGE ENTITY TRANSMITTAL FORM

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

May 24, 2004

Sir:

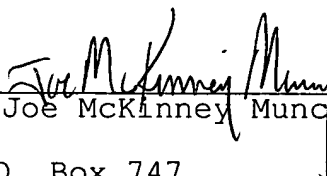
Transmitted herewith is a Reply to Restriction/Election Requirement in the above-identified application.

- ☐ The enclosed document is being transmitted via the Certificate of Mailing provisions of 37 C.F.R. § 1.8.
- ☐ Petition for _____ () month(s) extension of time pursuant to 37 C.F.R. §§ 1.17 and 1.136(a). \$0.00 for the extension of time.
- ☒ No fee is required.
- ☐ A check in the amount of \$0.00 is enclosed.
- ☐ Please charge Deposit Account No. 02-2448 in the amount of \$0.00. A triplicate copy of this sheet is attached.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. §§1.16 or 1.17; particularly, extension of time fees.

Respectfully submitted,

BIRCH, STEWART, KOLASCH & BIRCH, LLP

By 
Joe McKinney Mundy, #32,334

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0941-0754P

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Attachment(s)

(Rev. 02/08/2004)



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Applicant: LEE, Brian S. et al. Conf.: 7276
Appl. No.: 10/600,466 Group: 2811
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For: SEMICONDUCTOR DEVICE WITH LOOP LINE PATTERN
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REPLY TO RESTRICTION REQUIREMENT

Assistant Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

May 24, 2004

Sir:

Responsive to the Office Action dated May 6, 2004, the following election and remarks are respectfully submitted in connection with the above-identified application.

REMARKS

Claims 1-10 are now pending in the present application.

The Examiner has given the following Restriction Requirement:

Group I, claims 1-4, 7 and 8, drawn to a semiconductor device;

Group II, claims 9 and 10, drawn to a method of making a semiconductor device; and

Group III, claims 5 and 6, drawn to a phase-shift mask.

In response to this requirement, Applicants hereby elect Group 2, claims 9 and 10, drawn to a method of making a semiconductor device. This election is with traverse.

It is respectfully submitted that it should be no undue burden on the Examiner to consider all claims in the single application.